

"electronic additions" (i.e. surface adatoms or vacancies) that lead to electronic compensation and thus to

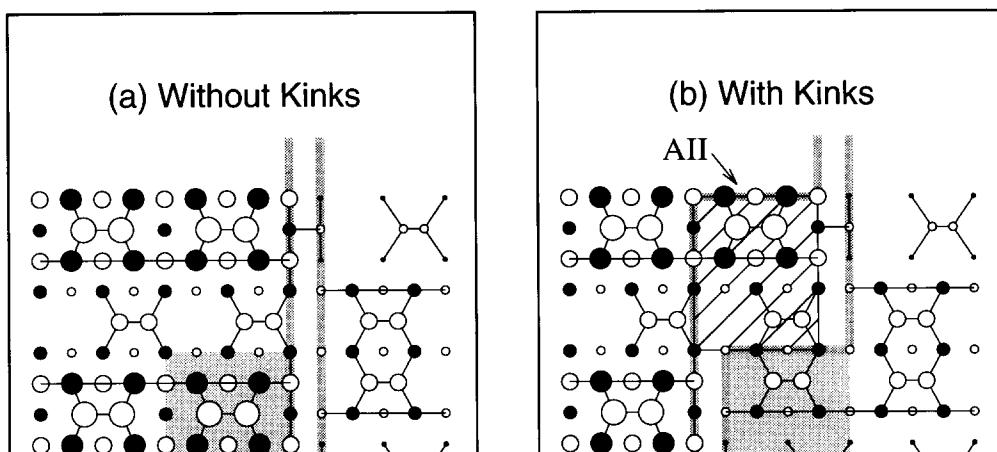
Previous studies of GaAs(001) surfaces [17] revealed that the net rule tends to be obeyed by these

stable and semiconducting flat surfaces. While step-step interaction has noticeable effects on step formation energies, the formation of steps is generally endothermic. There are two commonly observed steps:

~~those with edges parallel to the direction of surface As~~

motifs, leading to a set of point charges on various surface atoms. For example, Ga has 3 valence electrons, so fourfold coordinated $\text{Ga}^{(4)}$ contributes $3/4$ electrons to each of its four bonds. This leads to local charge neutrality. Planar $\text{Ga}^{(3)}$ is a $-2/4$ electron donor

Table 1
Coefficients $\omega_M(\sigma)$ denoting the frequency of motif M , coefficients N_k of the chemical potential terms in structure σ for (i) point defects, (ii) (001) surfaces and (iii) (001)–2×4 surface steps of GaAs and appropriate energies



4.2. Stability of A steps vs. B steps

Acknowledgments

As mentioned in Section 3.4, Heller et al. [5] have measured step energy by way of measuring the kink distribution on GaAs(001)- 2×4 . Depending on temperature, they obtained an A step formation energy

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include also the corner energies in Ref. [5]). Following Heller et al., one may derive from the calculated kink energy in Section 3.4 the A step formation energy. This gives 28–31 meV/(1×). Heller et al. also determined the B:A energy ratio to be 5.6–6. Ide et al. [7], on the contrary, estimated the ratio from measured anisotropy of equilibrium island shapes. Their values

References

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